

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Hiroshi IKEDA, et al.

GAU:

1754

SERIAL NO: 09/463,961

EXAMINER: T. VANOY

FILED:

May 25, 2000

FOR:

METHOD AND APPARATUS FOR PROCESSING EXHAUST GAS OF SEMICONDUCTOR

FABRICATION

REQUEST FOR EXTENSION OF TIME **UNDER 37 C.F.R. 1.136**

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

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It is hereby requested that a three month extension of time be granted to May 21, 2002 for

responding to the requirements in the Notice of Allowability dated:

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filing the Formal Drawings. The Issue Fee due

filing a response to the Official Action dated:

has been timely filed.

- responding to the Notice to File Missing Parts of Application dated:
- filing a Notice of Appeal. A timely response to the Final Rejection and a two month extension of time fee was filed on April 19, 2002.
- filing an Appeal Brief. A Notice of Appeal was filed on:
- ☐ Applicant claims small entity status. See 37 CFR 1.27. Therefore, the fee amount shown below is reduced by one-half.

The required fee of \$840.00 is enclosed herewith by check and any further charges may be made against the Attorney of Record's Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,

MAIER & NEUSTADT, P.C.

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